

L Number	Hits	Search Text	DB	Time stamp
1	13	vcsl and (specular near3 reflect\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:23
2	360	(reduc\$4 near3 (specular near3 reflect\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:54
3	2	((reduc\$4 near3 (specular near3 reflect\$3))) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:42
4	10	((reduc\$4 near3 (specular near3 reflect\$3))) and (semiconductor near3 laser)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:41
5	210	(low\$3 near3 (specular near3 reflect\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:41
6	2	((low\$3 near3 (specular near3 reflect\$4))) and (semiconductor near3 laser\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:42
7	0	((low\$3 near3 (specular near3 reflect\$4))) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:42
8	97	((low\$3 near3 (specular near3 reflect\$4))) and substrate\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:43
9	162	((reduc\$4 near3 (specular near3 reflect\$3))) and substrate\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:43
10	56	((reduc\$4 near3 (specular near3 reflect\$3))) and substrate\$1) and laser	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:43
12	1	((zero near3 order near3 (specular near3 reflect\$3))) and vcsl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:57
13	48	(grating near3 substrate) and vcsl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 10:58
14	0	(zero near3 order near3 (vcsl))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:08
11	44	(zero near3 order near3 (specular near3 reflect\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:42
15	0	vcsl and dbr and (substrate near3 low near3 reflect\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:51
16	112	vcsl and dbr and (substrate near3 reflect\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 12:06

17	88	(vcSEL and dbr and (substrate near3 reflect\$3)) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:53
18	0	substrate near3 antireflect\$3 near3 feature\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:55
19	1423	substrate near3 antireflect\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:55
20	0	(substrate near3 antireflect\$3) and vcSEL and dbr	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:55
21	12	(substrate near3 antireflect\$3) and dbr	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:56
22	533	(vcSEL or (surface near3 emit\$4)) and (specular near3 reflect\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 12:06
23	1	(substrate near3 antireflect\$3) and ((vcSEL or (surface near3 emit\$4)) and (specular near3 reflect\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 11:58
24	6	(vcSEL and dbr and (substrate near3 reflect\$3)) and ((vcSEL or (surface near3 emit\$4)) and (specular near3 reflect\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 12:01
25	70	(vcSEL or (surface near3 emit\$4)) and (specular near3 reflect\$3) and (substrate near3 reflect\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 12:41
26	6	vcSEL and dbr and (glare or (specular near3 reflect\$3)) and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 12:42
31	1		USPAT	2003/08/18 12:46
32	1		USPAT	2003/08/18 12:46
33	1		USPAT	2003/08/18 12:47
34	1		USPAT	2003/08/18 12:47
35	5	(substrate near3 scat\$7) AND (VCSEL OR (SURFACE NEAR3 emitting)) and dbr	USPAT; US-PGPUB	2003/08/18 12:50
36	5	(substrate near3 scat\$7) AND (VCSEL OR (SURFACE NEAR3 emitting)) and dbr	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 12:58
37	1029	(VCSEL OR (SURFACE NEAR3 emitting)) and dbr	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:02
38	7	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr) and (glare or (specular near3 reflect\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:00
39	2	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr) and (substrate near3 antireflect\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:01
40	934	(VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:03

41	881	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate) and reflect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:04
43	520	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate) and reflect\$4) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:04
42	122	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate) and reflect\$4) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:04
44	180	(pattern\$3 near3 substrate) and vcsel	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:51
45	0	((pattern\$3 near3 substrate) and vcsel) and reflect\$4 and (specular or diffuse\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 13:53
46	153	((pattern\$3 near3 substrate) and vcsel) and reflect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:21
47	295	vcsel and diffuse\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:21
48	108	vcsel and diffuse\$1 and dbr and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:21
49	55	vcsel and (reflect\$4 near3 (diffuse\$1 or scatter\$3)) and dbr and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:25
50	265	vcsel and dbr and substrate	USPAT	2003/08/18 14:25
52	197	(vcsel and dbr and substrate) and 372/\$.ccls.	USPAT	2003/08/18 14:26
51	47	(vcsel and dbr and substrate) and 438/\$.ccls.	USPAT	2003/08/18 14:28
53	5	vcsel and dbr and ((grat\$3 or step) near substrate)	USPAT	2003/08/18 14:32
54	0	vcsel and dbr and ((grat\$3) near substrate)	USPAT	2003/08/18 14:32
55	2	vcsel and dbr and ((grat\$3) near substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:33
56	1	(antireflection near grating) and substrate and dbr	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:35
57	6	(antireflection near grating) and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:39
58	4106	((specular near3 reflection) or glare) and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:41
59	11	(((specular near3 reflection) or glare) and substrate) and vcsel	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:41
64	1782	specular and scattering and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:07

65	10	(specular and scattering and substrate) and vcsel	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 14:53
66	121	specular and scattering and ((textured or rough\$4) near3 substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:27
68	0	(specular and scattering and ((textured or rough\$4) near3 substrate)) and vcsel	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:09
67	121	(specular and scattering and ((textured or rough\$4) near3 substrate)) and (vcsel or (surface emitting))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:09
70	72	(semiconductor near3 laser) and (semiconductor near3 substrate) and specular and reflect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:38
71	138	(semiconductor near3 substrate) and (specular near reflect\$4) and laser	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:39
72	5	((semiconductor near3 substrate) and (specular near reflect\$4) and laser) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:40
73	24	((semiconductor near3 substrate) and (specular near reflect\$4) and laser) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:43
74	127	vcsel and dbr and substrate and scattering	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:45
77	7	vcsel and dbr and substrate and specular	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:45
76	13	(vcsel and dbr and substrate and scattering) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:46
75	55	(vcsel and dbr and substrate and scattering) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:52
78	33	substrate near specular near reflect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:52
79	0	(substrate near specular near reflect\$4) and vcsel	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:53
80	0	(substrate near specular near reflect\$4) and surface near emitting near laser	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 15:53
81	1	vcsel and giro and grating and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:10
82	0	vcsel and specular and duffuse	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:10

83	8	vcSEL and specular and diffuse	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:10
84	14	(substrate near grating) and specular and diffuse	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:12
85	77	(semiconductor near laser) and specular and diffuse	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:13
86	71	(semiconductor near laser) and specular and diffuse and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:13
93	1		USPAT	2003/08/18 16:32
94	1		USPAT	2003/08/18 16:32
95	1		USPAT	2003/08/18 16:33
96	1		USPAT	2003/08/18 16:33
97	2229	(semiconductor near3 laser) and (pattern\$3 near3 substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:37
98	208	((semiconductor near3 laser) and (pattern\$3 near3 substrate)) and ((anti adj reflect\$3) or antireflect\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:38
99	18	((semiconductor near3 laser) and (pattern\$3 near3 substrate)) and ((anti adj reflect\$3) or antireflect\$3)) and specula\$5 and diffus\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 16:40
106	643	vcSEL and (scattering or diffus\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:26
107	209	(vcSEL and (scattering or diffus\$3)) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:24
108	117	vcSEL and ((scattering or diffus\$3) near3 (rays or beam))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:25
109	23	(vcSEL and ((scattering or diffus\$3) near3 (rays or beam))) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:27
110	226	vcSEL and (scattering or diffus\$3) and dbr	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:26
111	123	(vcSEL and (scattering or diffus\$3) and dbr) and 372/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:27
112	0	subwavelength near substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 17:40
113	12	subwavelength near structure	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 18:04
114	4	vcSEL near3 leak\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 18:06

115	2	vcsl and dbr and (grating near substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 18:09
116	177	vcsl and dbr and (grating and substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 18:09
117	78	vcsl and dbr and grating and substrate and (specular or diffus\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/18 18:10
118	1		USPAT	2003/08/18 18:19
119	1		USPAT	2003/08/18 18:19
120	1		USPAT	2003/08/18 18:19
121	1		USPAT	2003/08/18 18:19